b) Amendment to the Drawings

Please replace Fig. 2 with the attached new Fig. 2.

e) REMARKS

The claims are 1, 5-15 and 19-30, with claims 1 and 15 being independent. Claims 8, 10, 12-14, 22 and 25-28 have been amended as to form. Claims 2-4 and 16-18 have been cancelled and their subject matter added to independent claims 1 and 15, respectively. Non-elected claims 31-50 have been cancelled without prejudice to the filing of a division directed thereto. Reconsideration of the pending claims is expressly requested.

The Examiner objected to the specification and Fig. 2 on the ground that Fig. 2 should be referred to as PRIOR ART and the specification should be amended to be consistent therewith. Accordingly, as requested, a replacement sheet of drawings is enclosed in which Fig. 2 contains a PRIOR ART legend. In addition, the specification has been amended to identify Fig. 2 as PRIOR ART. Thus, the objection to the specification and Fig. 2 should be withdrawn.

Claims 3, 8, 10, 12-14, 17, 22, 24 and 26-28 were rejected under Rule 112, second paragraph, as being indefinite. Without necessarily agreeing or disagreeing, and solely to expedite prosecution, pending claims 8, 10, 22, 24 and 26-28 have been amended to address the Examiner's concerns. Withdrawal of the above rejection is respectfully requested.

Claims 1-5, 10, 15-19, 24, 29 and 30 were provisionally rejected as an obviousness-type double patenting over claims 1, 2, 5-8, 39-41, 42 and 44 of Application No. 10/776,173 ('173 application). This rejection is respectfully traversed.

The Examiner has recognized that there were specific claimed differences between the present claims and the claims of the copending '173 application. Claim 1 of

the copending application requires a trap means, while claim 39 provides that the emission intensity of a plasma on the side of the exhaust means of the chemical reaction causing means is smaller than the emission intensity of a plasma on the side of the processing chamber. These features are not claimed in the present invention. To the contrary, in the present claimed invention, the byproduct exhausted from the processing space chemically reacts without allowing plasma to reach the chemical reaction inducing means.

In addition, the copending application has not yet issued. If the provisional double patenting rejection is the sole remaining rejection, then the M.P.E.P. provides that the Examiner should allow the present application to issue.

Claims 1-3, 15-17, 29 and 30 were rejected as anticipated by Chiu '633.

Claims 1-3, 5, 12, 13, 15-17, 19, 26-27, 29 and 30 were rejected as anticipated by Pang '628. Without conceding the propriety of the rejections, it is submitted that the insertion of the subject matter of claim 4 into claim 1 and the insertion of the subject matter of claim 18 into claim 15 renders the above anticipation rejections moot.

Claims 1-4, 15-18, 29 and 30 were rejected over Ikeda JP '784 in view of Shoich JP '175 or Hideshige '174. Claims 5-14 and 19-28 were rejected as obvious over Chiu '633 or Pang '628 or Ikeda in view of Shoich or Hideshige, both in view of Kanai '257. The grounds of rejection are respectfully traversed.

Initially, it should be understood it is preferable to conduct a treatment of exhaust gas at a position closed to the processing space. When an exhaust treatment is conducted further from the processing space, any polymerized byproduct can clog an exhausting pipe and defeat the treatment.

Chiu '633 teaches that an exhaust treatment is conducted using a plasma

means. Accordingly, in Chiu, conducting an exhaust treatment in the vicinity of a

processing space without disturbing the plasma in the processing space is difficult. The

plasma of the treatment means tends to interfere with the plasma in the processing space.

To the contrary, in the present claimed invention, processing of the exhaust

is conducted using a heater, not a plasma. Therefore, it is possible to conduct the exhaust

treatment at a position close to the processing space. In Pang '628, trapping is conducted

employing a downstream plasma coating apparatus or a mechanical and/or electrostatic

trapping mechanism. Accordingly, Pang does not disclose employing a heater for exhaust

processing. Applicants do not understand that any of the Japanese references disclose that

the chemical reaction of the unreacted gas or byproduct is caused by heating a specific

metal member having a high melting point.

Wherefore, it is respectfully requested that the claims be allowed and that

the case be passed to issue.

Applicants' undersigned attorney may be reached in our New York office by

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Respectfully submitted,

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